

| Ref # | Hits | Search Query  | DBs   | Default Operator | Plurals | Time Stamp       |
|-------|------|---|---|------------------|---------|------------------|
| L1    | 259  | photolithograph? same ((focused near ion near beam) or "FIB") | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | OFF     | 2005/06/07 16:58 |
| L2    | 124  | 1 same pattern\$3   | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | OFF     | 2005/06/07 16:59 |
| L3    | 51   | 2 same mask\$3  | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | OFF     | 2005/06/07 16:59 |
| L4    | 20   | 3 and @pd<"20030214"  | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | OFF     | 2005/06/07 17:30 |
| L5    | 2142 | b82b003/00.ipc.   | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | OFF     | 2005/06/07 17:33 |
| L6    | 2    | 5 and ((nano near gap) same electrode)                        | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | OFF     | 2005/06/07 17:39 |
| L7    | 8    | 5 and (gap same electrode)                                    | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | OFF     | 2005/06/07 17:45 |
| L8    | 13   | 5 and (etch\$3 same electrode)                                | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | OFF     | 2005/06/07 17:39 |
| L9    | 12   | 8 not 7   | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | OFF     | 2005/06/07 17:43 |

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|-----|-------|--|---|----|-----|------------------|
| L10 | 1     | 204/192.1 and (nano near lithograph\$2)                                    | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | OFF | 2005/06/07 17:43 |
| L11 | 3546  | (nano or nanometer or "nm") same (electrode same (gap or distance))        | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | OFF | 2005/06/07 17:46 |
| L12 | 1     | 11 same ( "FIB" near lithograph\$2)  | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | OFF | 2005/06/07 17:53 |
| L13 | 2     | 11 same (( "FIB" or focused near ion near beam) same (metal same mask\$3)) | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | OFF | 2005/06/07 17:54 |
| L14 | 8     | 11 and (( "FIB" or focused near ion near beam) same (metal same mask\$3))  | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | OFF | 2005/06/07 17:55 |
| L15 | 6     | 14 not 13  | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | OFF | 2005/06/07 17:55 |
| L16 | 58715 | (etch\$3 or pattern\$3) same (electrode near layer or gold or "Au")        | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | OFF | 2005/06/07 18:07 |
| L17 | 6681  | 16 same (mask\$3 same (metal or titanium or "Ti"))                         | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | OFF | 2005/06/07 18:08 |
| L18 | 67    | 17 and (focused near ion near beam or "FIB")                               | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | OFF | 2005/06/07 18:09 |
| L19 | 45    | 18 and @pd<"20030214"  | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | OFF | 2005/06/07 18:09 |